

Photomask Blank and Method for Preparing Photomask

ABSTRACT

5 In a photomask blank comprising a transparent substrate,
a resistance layer, and a conductive layer, the resistivity
and thickness of the conductive layer and the resistivity and
thickness of the resistance layer are selected so as to meet
a specific equation (1). In EB lithography, a ground can be
10 established at a necessary fully low resistance value, and EB
writing be carried out at a high accuracy.

(No Suitable Figure)